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## Supporting Information

for

### **Polymer blend lithography: A versatile method to fabricate nanopatterned self-assembled monolayers**

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### **Snow-jet treatment of FDTS-SAM**

## Stability of FDTS-SAM against snow-jet treatment

The AFM pictures below show the stability of the FDTS-SAM against snow-jet treatment. The left picture was taken after a soft treatment, which lasted for about 30 seconds, while the right one was treated for 5 minutes. Both of the pictures have a scanning range of  $5 \times 5 \mu\text{m}$  and were taken in contact mode in water. The results show that there is no observable change of the depth of the holes after a thorough snow-jet treatment. This proves that the FDTS-SAM is stable against this lift-off method.

